

* * * * * Welcome to STN International * * * * *

<u>NEWS 1</u>		Web Page URLs for STN Seminar Schedule - N. America
<u>NEWS 2</u>		"Ask CAS" for self-help around the clock
<u>NEWS 3</u>	Feb 24	PCTGEN now available on STN
<u>NEWS 4</u>	Feb 24	TEMA now available on STN
<u>NEWS 5</u>	Feb 26	NTIS now allows simultaneous left and right truncation
<u>NEWS 6</u>	Feb 26	PCTFULL now contains images
<u>NEWS 7</u>	Mar 04	SDI PACKAGE for monthly delivery of multifile SDI results
<u>NEWS 8</u>	Mar 24	PATDPAFULL now available on STN
<u>NEWS 9</u>	Mar 24	Additional information for trade-named substances without structures available in REGISTRY
<u>NEWS 10</u>	Apr 11	Display formats in DGENE enhanced
<u>NEWS 11</u>	Apr 14	MEDLINE Reload
<u>NEWS 12</u>	Apr 17	Polymer searching in REGISTRY enhanced
<u>NEWS 13</u>	Jun 13	Indexing from 1947 to 1956 added to records in CA/CAPLUS
<u>NEWS 14</u>	Apr 21	New current-awareness alert (SDI) frequency in WPIDS/WPINDEX/WPIX
<u>NEWS 15</u>	Apr 28	RDISCLOSURE now available on STN
<u>NEWS 16</u>	May 05	Pharmacokinetic information and systematic chemical names added to PHAR
<u>NEWS 17</u>	May 15	MEDLINE file segment of TOXCENTER reloaded
<u>NEWS 18</u>	May 15	Supporter information for ENCOMPPAT and ENCOMPLIT updated
<u>NEWS 19</u>	May 19	Simultaneous left and right truncation added to WSCA
<u>NEWS 20</u>	May 19	RAPRA enhanced with new search field, simultaneous left and right truncation
<u>NEWS 21</u>	Jun 06	Simultaneous left and right truncation added to CBNB
<u>NEWS 22</u>	Jun 06	PASCAL enhanced with additional data
<u>NEWS 23</u>	Jun 20	2003 edition of the FSTA Thesaurus is now available
<u>NEWS 24</u>	Jun 25	HSDB has been reloaded
<u>NEWS 25</u>	Jul 16	Data from 1960-1976 added to RDISCLOSURE
<u>NEWS 26</u>	Jul 21	Identification of STN records implemented
<u>NEWS 27</u>	Jul 21	Polymer class term count added to REGISTRY
<u>NEWS 28</u>	Jul 22	INPADOC: Basic index (/BI) enhanced; Simultaneous Left and Right Truncation available

<u>NEWS EXPRESS</u>	April 4 CURRENT WINDOWS VERSION IS V6.01a, CURRENT MACINTOSH VERSION IS V6.0b(ENG) AND V6.0Jb(JP), AND CURRENT DISCOVER FILE IS DATED 01 APRIL 2003
<u>NEWS HOURS</u>	STN Operating Hours Plus Help Desk Availability
<u>NEWS INTER</u>	General Internet Information
<u>NEWS LOGIN</u>	Welcome Banner and News Items
<u>NEWS PHONE</u>	Direct Dial and Telecommunication Network Access to STN
<u>NEWS WWW</u>	CAS World Wide Web Site (general information)

Enter NEWS followed by the item number or name to see news on that specific topic.

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* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 14:14:16 ON 05 AUG 2003

=> file pnttext

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'EUROPATFULL' ENTERED AT 14:14:42 ON 05 AUG 2003
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FILE 'USPAT2' ENTERED AT 14:14:42 ON 05 AUG 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s Blomquist, Robert/in
'IN' IS NOT A VALID FIELD CODE
L1 18 BLOMQUIST, ROBERT/IN

=> s l1 and energy curable
L2 1 L1 AND ENERGY CURABLE

=> d

L2 ANSWER 1 OF 1 PCTFULL COPYRIGHT 2003 Univentio on STN

Full
Text

AN 2003011915 PCTFULL ED 20030228 EW 200307
TIEN FLUORINATED OPTICAL POLYMER COMPOSITION
TIFR COMPOSITION POLYMERE OPTIQUE FLUOREE
IN **BLOMQUIST, Robert, 30 Birch Hill Drive, Whippany, NJ 07981, US**
PA CORNING INCORPORATED, 1 Riverfront Plaza, Corning, NY 14831, US [US, US]
AG SUGGS, James, V, CORNING INCORPORATED, Patent Department, SP TI 3-1,
Corning, NY 14831, US
LAF English
LA English
DT Patent
PI WO 2003011915 A1 20030213
DS W: AE AG AL AM AT AU AZ BA BB BG BR BY BZ CA CH CN CO CR CU CZ
DE DK DM DZ EC EE ES FI GB GD GE GH GM HR HU ID IL IN IS JP
KE KG KP KR KZ LC LK LR LS LT LU LV MA MD MG MK MN MW MX MZ
NO NZ OM PH PL PT RO RU SD SE SG SI SK SL TJ TM TN TR TT TZ
UA UG UZ VN YU ZA ZM ZW
RW (EPO): AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR
AI WO 2002-US13673 A 20020429
PRAI US 2001-09/912,827 20010725
ICM C08F002-46
ICS G03C001-73; G03C001-725; G03C005-00; G02B006-10

=> s energy curable, (aromatic or heteroaromatic moiety), fluorinat?, ethylenicallu u
MISSING OPERATOR 'CURABLE, (AROMATIC'
The search profile that was entered contains terms or
nested terms that are not separated by a logical operator.

=> s energy curable and (aromatic or heteroaromatic moiety)
L3 263 ENERGY CURABLE AND (AROMATIC OR HETEROAROMATIC MOIETY)

=> s l3 and fluorinat?
L4 52 L3 AND FLUORINAT?

=> s l4 and ethylenically unsaturated
L5 19 L4 AND ETHYLENICALLY UNSATURATED

=> s 15 and initiator#
L6 14 L5 AND INITIATOR#

=> s 16 and isocyanurate moiety
L7 0 L6 AND ISOCYANURATE MOIETY

=> s 16 and isocyanurate
L8 6 L6 AND ISOCYANURATE

=> s 18 and compound#
L9 6 L8 AND COMPOUND#

=> s 19 and (polymer# or copolymer#)
L10 6 L9 AND (POLYMER# OR COPOLYMER#)

=> s 110 and optical element#
L11 0 L10 AND OPTICAL ELEMENT#

=> d 110 1-6

L10 ANSWER 1 OF 6 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full
Text

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 1025176 EUROPATFULL ED 20020605 EW 200221 FS PS
TIEN PROTECTIVE FILMS AND COATINGS.
TIDE SCHUTZSCHICHTEN UND BESCHICHTUNGEN.
TIFR FILMS ET REVETEMENTS PROTECTEURS.
IN BARRERA, Denise, A., P.O. Box 33427, Saint Paul, MN 55133-3427, US
PA MINNESOTA MINING AND MANUFACTURING COMPANY, 3M Center, P.O. Box 33427,
St. Paul, Minnesota 55133-3427, US
SO Wila-EPS-2002-H21-T1
DS R DE; R FR; R GB; R IT; R SE
PIT EPB1 EUROPAEISCHE PATENTSCHRIFT (Internationale Anmeldung)
PI EP 1025176 B1 20020522
OD 20000809
AI EP 1998-951044 19981013
PRAI US 1997-949367 19971014
RLI WO 98-US21514 981013 INTAKZ
WO 9919414 990422 INTPNR
REP US 4128600 A US 5009936 A
IC ICM C09J007-02
ICS B32B027-08

L10 ANSWER 2 OF 6 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 376655 EUROPATFULL ED 20000910 EW 199027 FS OS STA B
TIEN Photographic element and preparation thereof.
TIDE Photographisches Element und dessen Herstellung.
TIFR Element photographique et sa preparation.
IN Kobayashi, Tohru Konica Corporation, 26-2 Nishi-shinjuku 1-chome
Shinjuku-ku, Tokyo, JP;
Nishi, Yasuo Konica Corporation, 26-2 Nishi-shinjuku 1-chome
Shinjuku-ku, Tokyo, JP;
Nakano, Nakaya Konica Corporation, 26-2 Nishi-shinjuku 1-chome
Shinjuku-ku, Tokyo, JP;
Ohkawa, Kazuo c/o Asahi Denka Kogyo K.K., 2-35 Higashi-ogu 7-chome

Arawaka-ku, Tokyo, JP;
Tachikawa, Hiroyuki c/o Asahi Denka Kogyo K.K., 2-35 Higashi-ogu 7-chome
Arawaka-ku, Tokyo, JP
PA KONICA CORPORATION, No. 26-2, Nishishinjuku 1-chome Shinjuku-ku, Tokyo,
JP;
ASAHI DENKA KOGYO KABUSHIKI KAISHA, 2-35, Higashiogu 7-chome, Arakawa-ku
Tokyo 116, JP
SO Wila-EPZ-1990-H27-T2
DS R DE; R GB; R NL
PIT EPA2 EUROPÄISCHE PATENTANMELDUNG
PI EP 376655 A2 19900704
OD 19900704
AI EP 1989-313525 19891222
PRAI JP 1988-335608 19881229
IC ICM G03C011-08

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 376655 EUROPATFULL UP 20010712 EW 199540 FS PS STA B
TIEN Photographic element and preparation thereof.
TIDE Photographisches Element und dessen Herstellung.
TIFR Element photographique et sa preparation.
IN Kobayashi, Tohru Konica Corporation, 26-2 Nishi-shinjuku 1-chome
Shinjuku-ku, Tokyo, JP;
Nishi, Yasuo Konica Corporation, 26-2 Nishi-shinjuku 1-chome
Shinjuku-ku, Tokyo, JP;
Nakano, Nakaya Konica Corporation, 26-2 Nishi-shinjuku 1-chome
Shinjuku-ku, Tokyo, JP;
Ohkawa, Kazuo c/o Asahi Denka Kogyo K.K., 2-35 Higashi-ogu 7-chome
Arawaka-ku, Tokyo, JP;
Tachikawa, Hiroyuki c/o Asahi Denka Kogyo K.K., 2-35 Higashi-ogu 7-chome
Arawaka-ku, Tokyo, JP
PA KONICA CORPORATION, 26-2, Nishishinjuku 1-chome, Shinjuku-ku, Tokyo 160,
JP;
ASAHI DENKA KOGYO KABUSHIKI KAISHA, 2-35, Higashiogu 7-chome, Arakawa-ku
Tokyo 116, JP
SO Wila-EPS-1995-H40-T2
DS R DE; R GB; R NL
PIT EPB1 EUROPÄISCHE PATENTSCHRIFT
PI EP 376655 B1 19951004
OD 19900704
AI EP 1989-313525 19891222
PRAI JP 1988-335608 19881229
REP US 4426431 A
REN PATENT ABSTRACTS OF JAPAN, vol. 11, no. 201 (P-500) (2648) 30 June 1987 &
JP-A-62 021 150 Ronald S. Bauer (ED) 'Epoxy Resin Chemistry' 1981,
American Chemical Society, Washington US, Chapter 2, "Photosensitized
epoxides as basis for light-curable coatings", pp. 17-45
IC ICM G03C011-08

L10 ANSWER 3 OF 6 PCTFULL COPYRIGHT 2003 Univentio on STN

Full
Text

AN 2002090412 PCTFULL ED 20021121 EW 200246
TIEN **ENERGY CURABLE** ADDUCT CONTAINING A FLUORO GROUP AND COATINGS THEREFROM
TIFR PRODUIT D'ADDITION POUVANT ETRE DURCI PAR DE L'ENERGIE, CONTENANT UN
GROUPE FLUORO, ET REVETEMENTS FABRIQUES A PARTIR DUDIT PRODUIT
IN BIRCH, Adrian, J., La Traviata, Slnt-Jansteen 4564ER, NL [GB, NL];
DUFF, Alan, W., Saxhavenstraat 10, Hulst 4561HC, NL [GB, NL];
BARTELINK, Camiel, F., Robijnboog 31, Terneuzen 4533BA, NL [NL, NL]
PA DOW GLOBAL TECHNOLOGIES INC., Washington Street, 1790 Building, Midland,
MI 48674, US [US, US], for all designates States except US;
BIRCH, Adrian, J., La Traviata, Slnt-Jansteen 4564ER, NL [GB, NL], for
US only;

DUFF, Alan, W., Saxhavenstraat 10, Hulst 4561HC, NL [GB, NL], for US only;
 BARTELINK, Camiel, F., Robijnboog 31, Terneuzen 4533BA, NL [NL, NL], for US only
 AG ULMER, Duane, C., The Dow Chemical Company, Intellectual Property, B-1211, 2301 North Brazosport Boulevard, Freeport, TX 77541, US
 LAF English
 LA English
 DT Patent
 PI WO 2002090412 A1 20021114
 DS W: AE AG AL AM AT AU AZ BA BB BG BR BY BZ CA CH CN CO CR CZ DE DK DM DZ EC EE ES FI GB GD GE GH GM HR HU ID IL IN IS JP KE KG KR KZ LC LK LR LS LT LU LV MA MD MG MK MN MW MX MZ NO NZ OM PH PL PT RO RU SD SE SG SI SK SL TJ TM TN TR TT TZ UA UG US UZ YU ZA ZM ZW
 RW (ARIPO): GH GM KE LS MW MZ SD SL SZ TZ UG ZM ZW
 RW (EAPO): AM AZ BY KG KZ MD RU TJ TM
 RW (EPO): AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR
 RW (OAPI): BF BJ CF CG CI CM GA GN GQ GW ML MR NE SN TD TG
 AI WO 2002-US14309 A 20020507
 PRAI US 2001-60/289,344 20010507
 ICM C08G018-10
 ICS C08G018-28; C08G018-67; C08G018-48; C08G018-75

L10 ANSWER 4 OF 6 PCTFULL COPYRIGHT 2003 Univentio on STN

Full
Text

AN 1999019414 PCTFULL ED 20020515
 TIEN PROTECTIVE FILMS AND COATINGS
 TIFR FILMS ET REVETEMENTS PROTECTEURS
 IN BARRERA, Denise, A.
 PA MINNESOTA MINING AND MANUFACTURING COMPANY
 LA English
 DT Patent
 PI WO 9919414 A1 19990422
 DS W: AL AM AT AU AZ BA BB BG BR BY CA CH CN CU CZ DE DK EE ES FI GB GD GE GH GM HR HU ID IL IS JP KE KG KP KR KZ LC LK LR LS LT LU LV MD MG MK MN MW MX NO NZ PL PT RO RU SD SE SG SI SK SL TJ TM TR TT UA UG UZ VN YU ZW GH GM KE LS MW SD SZ UG ZW AM AZ BY KG KZ MD RU TJ TM AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE BF BJ CF CG CI CM GA GN GW ML MR NE SN TD TG
 AI WO 1998-US21514 A 19981013
 PRAI US 1997-08/949,367 19971014
 ICM C09J007-02
 ICS B32B027-08

L10 ANSWER 5 OF 6 USPATFULL on STN

Full
Text

Citing
References

AN 1999:124593 USPATFULL
 TI Protective films and coatings
 IN Barrera, Denise A., Oakdale, MN, United States
 PA Minnesota Mining and Manufacturing Company, St. Paul, MN, United States (U.S. corporation)
 PI US 5965256 19991012
 AI US 1997-949367 19971014 (8)
 DT Utility
 FS Granted
 LN.CNT 1325
 INCL INCLM: 428/354.000
 INCLS: 428/201.000; 428/203.000; 428/204.000; 428/421.000; 428/422.000; 428/423.100; 428/424.200; 428/424.400; 428/522.000; 427/487.000; 427/508.000; 427/521.000; 427/522.000; 427/407.100; 526/245.000;

525/123.000; 525/126.000

NCL NCLM: 428/354.000
 NCLS: 427/407.100; 427/487.000; 427/508.000; 427/521.000; 427/522.000;
 428/201.000; 428/203.000; 428/204.000; 428/421.000; 428/422.000;
 428/423.100; 428/424.200; 428/424.400; 428/522.000; 525/123.000;
 525/126.000; 526/245.000

IC [6]
 ICM: B32B027-08
 ICS: B32B027-16; B32B027-30; B32B027-40

EXF 428/201; 428/202; 428/203; 428/353; 428/354; 428/421; 428/422;
 428/423.1; 428/424.2; 428/424.4; 428/522; 526/245; 525/123; 525/126;
 427/487; 427/508; 427/521; 427/407.1

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L10 ANSWER 6 OF 6 USPATFULL on STN

Full Text	Citing References
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AN 93:3477 USPATFULL

TI Method of making photographic element having epoxy overlayer

IN Kobayashi, Tohru, Hino, Japan
 Nishi, Yasuo, Hino, Japan
 Nakano, Nakaya, Hino, Japan
 Ohkawa, Kazuo, Tokyo, Japan
 Tachikawa, Hiroyuki, Tokyo, Japan

PA Konica Corporation, Tokyo, Japan (non-U.S. corporation)
 Asahi Denka Kogyo K.K., Tokyo, Japan (non-U.S. corporation)

PI US 5178996 19930112

AI US 1992-897578 19920611 (7)

RLI Continuation of Ser. No. US 1991-670371, filed on 14 Mar 1991, now
 abandoned which is a continuation of Ser. No. US 1989-458303, filed on
 28 Dec 1989, now abandoned

PRAI JP 1988-335608 19881229

DT Utility

FS Granted

LN.CNT 986

INCL INCLM: 430/532.000
 INCLS: 427/331.000; 430/271.000; 430/273.000; 430/523.000; 430/531.000;
 430/961.000

NCL NCLM: 430/532.000
 NCLS: 427/331.000; 430/271.100; 430/273.100; 430/523.000; 430/531.000;
 430/961.000

IC [5]
 ICM: G03C001-76

EXF 430/271; 430/273; 430/523; 430/531; 430/532; 430/961; 427/331

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

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